

Notice of References Cited		Application No. <i>10/635,574</i>		Applicant(s) <i>Kaneko et al</i>		
		Examiner <i>M.L. Padgett</i>		Group Art Unit <i>1762</i>		
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*	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	
A	<i>2,970,988</i>	<i>2/7/61</i>	<i>Elizabeth LO</i>	<i>260</i>	<i>87.7</i>	
B	<i>5,475,071</i>	<i>12/1995</i>	<i>Smart et al</i>	<i>526</i>	<i>247</i>	
C	<i>4,654,394</i>	<i>3/31/1987</i>	<i>Yamake et al</i>	<i>526</i>	<i>247</i>	
D	<i>6,670,511 B2</i>	<i>12/30/2003</i>	<i>Kashiwaga et al</i>	<i>528</i>	<i>683</i>	
E	<i>5,260,492</i>	<i>11/9/93</i>	<i>Feiring et al</i>	<i>528</i>	<i>685</i>	
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G						
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X	<i>N WO 02/065212A1</i>	<i>Aug 22, 2002</i>	<i>PCT</i>	<i>(Applicants) Kaneko et al</i>		
O	<i>WO 00/17712</i>	<i>March 2000</i>	<i>PCT</i>	<i>Feiring</i>		
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NON-PATENT DOCUMENTS						
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U	<i>Toriumi et al, "Resist materials for 157-nm Lithography"; Advances in Resist Technology & Processing XVII, F. Houlihan, ed., Proceedings of SPIE, Vol. 4345, p. 371-378</i>				<i>Feb 2001</i>	
V	<i>Ito et al, "Polymer design for 157nm chemically amplified resins"; F. Houlihan, ed, Advances in Resist Tech. & Processing XVII, Proceedings of SPIE, Vol. 4345, p. 273-284</i>				<i>Feb 2001</i>	
W	<i>Toriumi et al, "Fluoropolymer based resist for a single-resist process of 157nm Lithography"; J. Vac. Sci. Technol. B, 20(6), p. 2909-2912</i>				<i>Nov/Dec 2002</i>	
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* A copy of this reference is not being furnished with this Office action.
(See Manual of Patent Examining Procedure, Section 707.05(a).)